

## METHOD AND SYSTEM FOR IMMERSION LITHOGRAPHY LENS CLEANING

### ABSTRACT

[0037] A method and system for cleaning lens used in an immersion lithography system is disclosed. After positioning a wafer in the immersion lithography system, a light exposing operation is performed on the wafer using an objective lens immersed in a first fluid containing surfactant, wherein the surfactant reduces a likelihood for having floating defects adhere to the wafer and the objective lens.

50396\_4.DOC